Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	1	("20040035153").PN.	US-PGPUB; USPAT	OR	OFF	2005/08/13 10:00
S2	1	("5942356").PN.	US-PGPUB; USPAT	OR	OFF	2005/08/12 14:45
S3	4	(mask or photomask or reticle) same glass near2 (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) near2 (silica or silicon dioxide or SiO".sub.2")	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 13:49
S4	0	(mask or photomask or reticle) same glass near2 (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") not S3	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 13:49
S5	16	(mask or photomask or reticle) same glass same (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") not S3 not S4	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 13:50
S6	2301	((mask or photomask or reticle) near3 (phase or shift$3 or reflect$3 or extreme ultraviolet or extreme UV or EUV) or PSM) same glass not S3 not S4 not S5	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 14:09
S7	74	S6 and glass same (polish$3 or abra$4 or grind$3) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 14:11
S8	131	S6 and glass same (polish$3 or abra$4 or grind$3) not S7	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 14:25
S9	1790	430/5.ccls. and (mask or photomask or reticle) same glass same (blank or base or substrate) not S3 not S5 not S7 not S8	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 14:20
S10	500	S6 and S9	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 14:21
S11	4	S10 and (polish$3 or abra$4 or grind$3) same (silica or silicon dioxide or SiO".sub.2" or SiO$6) not S3 not S5 not S7 not S8	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 14:28

S12	546	(451/36,37,41,42,390.ccls. or 65/60.1, 61.ccls. or 427/160,165,290,292.ccls.) and (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6) not S3 not S5 not S7 not S8 not S11	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 14:36
S13	458	S12 and (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 14:46
S14	3	S13 and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 14:44
S15	386	S13 and (polish$3 or abra$4 or grind$3) same (pressure or force or load) not S14	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 14:49
S16	49	S15 and (pressure or force or load) same glass	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 14:50
S17	1346	51/308.ccls. not S3 not S5 not S7 not S8 not S11 not S14 not S16	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 14:52
S18	2	S17 and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 14:54
S19	3	S17 and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) not S18	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 14:58
S20	67	S17 and hydroly$4 with (silica or silicon dioxide or SiO".sub.2" or SiO$6) not S18 not S19	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:00
S21	5	S20 and hydroly$4 same (silicon or Si) with (organic or polymer) not S18 not S19	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:04
S22	3	S20 and hydroly$4 same (silicon or Si) same (organic or polymer) not S21	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:04
S23	12	(Kesahiro near2 Koike or Junji near2 Miyagaki).in. not S3 not S5 not S7 not S8 not S14 not S16 not S18 not S19 not S21 not S22	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:20

S24	4	(mask or photomask or reticle) same glass near2 (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) near2 (silica or silicon dioxide or SiO".sub.2")	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S25	0	(mask or photomask or reticle) same glass near2 (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") not S24	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S26	16	(mask or photomask or reticle) same glass same (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") not S24 not S25	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S27	2301	((mask or photomask or reticle) near3 (phase or shift$3 or reflect$3 or extreme ultraviolet or extreme UV or EUV) or PSM) same glass not S24 not S25 not S26	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S28	74	S27 and glass same (polish$3 or abra$4 or grind$3) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S29	131	S27 and glass same (polish$3 or abra$4 or grind$3) not S28	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S30	1790	430/5.ccls. and (mask or photomask or reticle) same glass same (blank or base or substrate) not S24 not S26 not S28 not S29	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S31	500	S27 and S30	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S32	4	S31 and (polish$3 or abra$4 or grind$3) same (silica or silicon dioxide or SiO".sub.2" or SiO$6) not S24 not S26 not S28 not S29	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S33	546	(451/36,37,41,42,390.ccls. or 65/60.1, 61.ccls. or 427/160,165,290,292.ccls.) and (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6) not S24 not S26 not S28 not S29 not S32	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S34	458	S33 and (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24

S35	3	S34 and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S36	386	S34 and (polish$3 or abra$4 or grind$3) same (pressure or force or load) not S35	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S37	49	S36 and (pressure or force or load) same glass	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S38	1346	51/308.ccls. not S24 not S26 not S28 not S29 not S32 not S35 not S37	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S39	2	S38 and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S40	3	S38 and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) not S39	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S41	67	S38 and hydroly$4 with (silica or silicon dioxide or SiO".sub.2" or SiO$6) not S39 not S40	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S42	5	S41 and hydroly$4 same (silicon or Si) with (organic or polymer) not S39 not S40	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S43	3	S41 and hydroly$4 same (silicon or Si) same (organic or polymer) not S42	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S44	12	(Kesahiro near2 Koike or Junji near2 Miyagaki).in. not S24 not S26 not S28 not S29 not S35 not S37 not S39 not S40 not S42 not S43	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:24
S45	1033	(polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") same (alkali metal or sodium or potassium or "Na" or "K") not S24 not S26 not S28 not S29 not S35 not S37 not S39 not S40 not S42 not S43 not S44	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:33

S46	79	S45 and 51/308.ccls. and (colloid$2) same (silica or silicon dioxide or SiO".sub.2") same (alkali metal or sodium or potassium or "Na" or "K")	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:38
S47	19	S46 and (alkali metal or sodium or potassium or "Na" or "K") same impur$5	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	ADJ	ON	2005/08/13 15:39